



AF ZPW

PATENT  
Customer No. 22,852  
Attorney Docket No. 4329.2543-01

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:	)	
	)	
Masamitsu Itoh et al.	)	Group Art Unit: 1752
	)	
Application No.: 10/665,616	)	Examiner: Amanda C. Walke
	)	
Filed: September 22, 2003	)	
	)	
For: PATTERN FORMATION	)	Confirmation No.: 6561
MATERIAL, PATTERN	)	
FORMATION METHOD, AND	)	
EXPOSURE MASK	)	
FABRICATION METHOD	)	

Mail Stop AF  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

**REQUEST FOR RECONSIDERATION**

In reply to the Final Office Action mailed December 21, 2004, the period for response extending through March 21, 2005, Applicants submit the following remarks.

**Attachments** to this amendment include a partial translation of Sato et al.

(JP 09-262721).

Do Not  
Enter SCW  
4/6/05